



**Bay Area Chrome Users Society
3rd Annual Symposium
September 14 and 15, 1983
Santa Clara, California**

BAY AREA CHROME USERS SOCIETY
SYMPOSIUM

SEPTEMBER 1983
SANTA CLARA, CALIFORNIA

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WELCOME NOTE
Bacus Symposium
September 14 & 15, 1983
Sunnyvale Hilton Inn, Sunnyvale, CA

Good evening, everybody, my name is Jim Wiley. I'm the president of the Bay Area Chrome Users Society. I'm from Master Images, and I'm going to be your host for the Third Symposium of the Bacus Organization this evening and tomorrow.

It's a great feeling to see so many friends out there. We've got a hundred and fifty people out here tonight and that represents an increase from one hundred and twenty paid registrants last year and eighty for the first conference. So this organization has doubled in two years. It has also matured a great deal. The first year we made a program by calling up the ten mask vendors and telling them that they had to give a paper or they couldn't come. And then we tried to convince them we wouldn't buy from them if they didn't give a paper.

This year, we've progressed far past that. We just twisted arms. We've got a collection that includes a fair number of papers from users, in addition to suppliers and that represents quite a cross section of the entire mask making and semiconductor photolithography field.

The theme for the conference this year is Mask and Materials For One to Two Micron Lithography. We're talking one to two microns on the wafer. We are specifically including ten to twenty micron 10x reticles and 5 to 10 micron 5x reticles. Am I leaving out 7x or something? Every scale that you want to talk about as we're dealing with the problem of making mask and materials for the final result of semiconductor lithography being 1 to 2 microns.

Because of the roots of this organization being in the chrome blanks (and we want to continue the emphasis on that), we've tried to keep the conference focused on things that are affected by chrome blanks and that is critical dimension, defects and flatness. We tried to leave out, in general, the discussion of large area registration control, but that'll sneak in too, because you can't talk about 1 to 2 micron wafer lithography without that.

I'd like to introduce to you this evening the Bacus Conference Committee that was responsible for putting together this program. The people that helped with the twisting of arms come to mind first. Steve Dunbrack is our paper's chairman. I'd like to ask Steve to stand up. Paul you're next since you helped twist a few arms also. Could we have Steve Dunbrack and Paul Johnson stand up. Larry Zurbrick is our finance director.

The printing of the programs and the arrangements for publicity, signs and the proceedings are being handled by Bud Manzler.

Registration is being handled by Ron Ivancich, who is here just finishing up his meal I think. Facilities and arrangements have been handled by Ron Johnstone. He's also handling the Paul Masson Mountain Vineyard Dinner and Wine Tasting tomorrow night. Let's have a big hand for Ron. Our publicity chairman and secretary is Jeremy Nichols. And our projection and audio-visual coordinator is Ray Chin. I think that covers it.

Now Ron is someone you might need to know. Because as of now there are no seats available for tomorrow night's dinner; so talk about arm twisting. We've guaranteed 140 seats and we have 140 seats and we have 140 paid attendees. If anybody has paid and is not attending, we would like to sell your ticket to somebody else. Speakers in particular have been given complimentary registrations to the conference and the Paul Masson Vineyard. If you're not attending please let Ray Chin know. He's handling three things for the speakers. One, he's handling the collection of slides, the collection of biographies for introduction. Please tell him if you are or are not attending the Great Moments in Mask Making historical address tomorrow night.

I'd like to acknowledge that we have had sponsorship and financial contributions by several organizations and I'm going to spread it out over the conference and these acknowledgements. The first organization to contribute came from Ultratech Photo Mask, and the sister organization over in Milpitas, Ultra Glass. They are credited for this evening's reception.

Now to the important things, current events. FLASH, the USA's Liberty has won over the winged keel Australia II by over one minute. We can do it, right?

Okay, to keep track of what's going on here, I'd like to call your attention in your registration packet, to the smallest thing in there, the most frequently needed-to-be-referred-to-thing. This is your program. It says that we were going to start talking a few minutes ago, so I'm going to have to move on. But this will confirm that the next two meeting times that we have to worry about are, number one, 8:00 tomorrow morning. We have coffee and donuts in the back room. Number two, 8:25 we'll be calling the meeting to order. Then 4:30 tomorrow we're going to convene. At 6:00 we're due at the Paul Masson Mountain Vineyard. The Vineyard is several miles past Paul Masson Winery, up the hill. There are maps that have been passed out to you and we'll meet there at 6:00 for wine tasting and a steak dinner, and whatever corruption Jim Reynolds, excuse me, the historical address that's being fumbled by, I mean coordinated by, Jim Reynolds.